Docket No.: N.C. 84,613

ÉD STATES PATENT AND TRADEMARK OFFICE

Applicants

Walton et al.

Appl. No.

10/644,567

Filed

August 20, 2003

Title

ELECTRON BEAM ENHANCED LARGE AREA DEPOSITION

SYSTEM

Art Unit

Not yet assigned

Examiner

Not yet assigned

Honorable Assistant Commissioner for Patents Washington, DC 20231

INFORMATION DISCLOSURE STATEMENT

Sir:

Applicants wish to advise the Patent and Trademark Office of the information listed on the attached Form PTO/SB/08 considered during the preparation of the above-identified application. A copy of each of the references listed is enclosed.

Kindly charge any additional fees due, or credit overpayment of fees, to Deposit Account No. 50-0281.

Respectfully submitted,

Prepared by:

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(202) 404-1554

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Reg. No. 36,182 Associate Counsel (Patents)

Naval Research Laboratory

4555 Overlook Avenue, S.W. Washington, D.C. 20375-5325

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INFORMATION DISCLOSURE STATEMENT BY APPLICANT (use as many sheets as necessary)	Application Number	10/644,567					
	Filing Date	August 20, 2003					
STATEMENT BY APPLICANT			PPLICANT	First Named Inventor	Walton et al.		
				Group Art Unit	Not yet assigned		
(use as many sheets as necessary)		Examiner Name	Not yet assigned				
Sheet	1	of 2	2	Attorney Docket Number	84.613		

	U.S. PATENT DOCUMENTS							
Examiner Initials	Cite No.1	U.S. Patent Number	Document Kind Code ² (if known)	or Cited Document	Date of Publication of Cited Document MM-DD-YYYY	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear		
		5,182,496		Manheimer et al.	01-26-1993			
		5,874,807		Neger et al.	02-23-1999			
					 			
								
								

	FOREIGN PATENT DOCUMENTS											
Examiner	Cite	Foreign Patent Document Name of Patentee or				Foreign Patent Document			Name of Patentee or	Date of Publication of	Pages, Columns, Lines, Where Relevant	Т
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Group Art Unit Not yet assigned

Examiner Name Not yet assigned

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Sheet 2 of 2

OTHER PRIOR ART - NON PATENT LITERATURE DOCUMENTS Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the Examiner Cite item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), Initials No. publisher, city and/or country where published. R. F. FERNSLER ET AL., "Production of large-area plasmas by electron beams," Phys. Plasmas, 1998, 5, 2137-2143 WALLACE M. MANHEIMER ET AL., "Theoretical overview of the large-area plasma processing system (LAPPS)," Plasma Sources Sci. Technol. 2000, 9, 370-386 S. G. WALTON ET AL., "Ion energy distributions in a pulsed, electron beam-generated plasma," J. Vac. Sci. Technol. A, 2001, 19(4), 1325-1329 D. LEONHARDT ET AL., "Plasma diagnostics in large area plasma processing system," J. Vac. Sci. Technol. A, 2001, 19(4), 1367-1373 R. A. MEGER ET AL., "Beam-generated plasmas for processing applications," Phys Plasmas, 2001, 8, 2558-2564 KARL-HEINZ MULLER, "Stress and microstructure of sputter-deposited thin films: Molecular dynamcis investigations," J. Appl. Phys., 1987, 62, 1796-1799

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Application Number 10/644,567 Filing Date August 20, 2003 First Named Inventor Walton et al. Group Art Unit Not yet assigned **Examiner Name** Not yet assigned Attorney Docket Number

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7				U.S. PATENT DOCU	MENTS	
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		5,874,807		Neger et al.	02-23-1999	
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y/	7	OTHER PRIOR ART - NON PATENT LITERATURE DOCUMENTS	
Examiner Initials	Cite No.1	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T
		R. F. FERNSLER ET AL., "Production of large-area plasmas by electron beams," Phys. Plasmas, 1998, 5, 2137-2143	
		WALLACE M. MANHEIMER ET AL., "Theoretical overview of the large-area plasma processing system (LAPPS)," Plasma Sources Sci. Technol. 2000, 9, 370-386	
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